

Abstract of the Disclosure

A semiconductor manufacturing station (50) exposes light on a surface area of a spherical semiconductor device or ball (52). A mask pattern generator (56) provides a pattern of light, which undergoes temporal changes to collectively represent an image. The mask pattern generator has an active exposure contour (80) that provides a portion of the overall image. The 10 pattern of light is directed through a lens (62) to the surface area of the semiconductor device. The semiconductor device rotates in relation to the temporal changes in the pattern of light to expose the pattern of light over a portion of a surface area of the 15 semiconductor device. The exposure contour has a narrower center and becomes wider moving away from the center. The exposure contour may have a curvature.